

ABSTRACT OF THE DISCLOSURE

A method of forming a conductive device includes forming a conductive layer on a substrate; etching the conductive layer to form a plurality of conductive traces; etching the conductive layer to form at least one mask feature; 5 and removing substrate material that is not covered by the at least one mask feature so as to form at least one mechanical alignment feature.

DRAFTING STANDARDS - 400-4000-00000

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